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(54) Title: SURFACE ACTIVATED CHEMICAL VAPOR DEPOSITION AND USES THEREOF

(57) Abstract: Surface activated chemical vapor deposition (SACVD) methods and uses thereof are described herein. Polymeric coatings deposited by SACVD demonstrate high uniformity and conformality, as compared to other deposition techniques, such as initiated chemical vapor deposition (iCVD). Such polymeric coatings are useful for various applications, such as semiconductor applications.

WO 2025/007115 A2